## **ACKNOWLEDGEMENT RECEIPT**

Electronic Version 1.1

Stylesheet Version v1.1.1

Title of Invention

HIGH PRESSURE PROCESSING CHAMBER FOR SEMICONDUCTOR SUBSTRATE

Submision Type: Information Disclosure

Statement

**Application Number:** 

09/912844

EFS ID: 81783

Server Response:

Confirmation Code	Message
	Submission was successfully submitted - Even if Informational or Warning Messages appear below, please do not resubmit this application
ICON1	5915
	Eer assistance with e-filing a patent application, contact the Patent Electronic Business Center: Toll-Free Number:1(866) 217-9197 Website: http://www.uspto.gov/ebc/

First Named Applicant: Maximilian Biberger

Attorney Docket Number:

Timestamp: 2005-04-07 18:10:23 EDT

From: us

File Listing:

Doc. Name	File Name	Size (Bytes)	Date
			Produced
			(yyyymmdd)
us-ids	SSI_00501-usidst.xml	1547	2005-04-07
us-ids	us-ids.dtd	7763	2005-04-07
us-ids	us-ids.xsl	12026	2005-04-07
package-data	SSI_00501-pkda.xml	1713	2005-04-07
package-data	package-data.dtd	27025	2005-04-07
package-data	us-package-data.xsl	19263	2005-04-07
Total files size		69337	

Message Digest: cbee633fd7becac1e013687b5e61923f53ff61e1

Digital Certificate Holder C

Name:

cn=Thomas B.

Haverstock,ou=Registered Attorneys,ou=Patent and

Trademark

Office,ou=Department of

Commerce,o=U.S. Government,c=US